

# Wrap Up

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Accelerating the next technology revolution.

# Topics for Next TWG

- **Outgassing? Keep in Optics TWG, but include “pass down”**
- **Regional updates? Short presentations are good.**
- **Exposure tool dose calibrations and comparisons? Report Ezero from Berkeley calibration line, MET-2D at next meeting. Also calibrate MET to Ezero and then collect Esize. Do experiment at thinner resist. (Naulleau)**
- **Share resist screening data? No comments, data shown at conference.**
- **22 nm resists? Invited talk by university or research , not covered at conference?**
- **16nm resists?**
- **LER/LWR of devices or etched features (EUV)?**
- **Aspect ratio, thin film effects?**



# Plans for Next TWG Meetings

- **Teleconference mid-July**
- **EUVL Symposium, Oct. 29-31, 2007**
  - **Sapporo, Japan**
  - **Larger room, please**